

June 15, 2001

Via Federal Express

Leon Radomsky, Esq.
Foley & Lardner
3000 K Street N.W., Suite 500
Washington, D.C. 20007-5109

Re: Formal Paperwork for:

AMD's reference: F0822
Your reference: 039153-0381
Inventors: Ramkumar Subramanian, et al.
Title: "Two Mask Photoresist Exposure Pattern
For Dense And Isolated Regions"

Dear Mr. Radomsky:

Enclosed are the executed formal documents for the above-identified AMD case.

Thank you and regards,



Winona C. Orange
Administrative Specialist
Technology Law Department

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Enclosures